

Spin coater

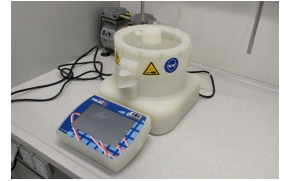
<https://search.labfacilities.wur.nl/SearchDetail.aspx?deviceid=eeb1b990-503f-405f-8fe0-a241c7478a92>

Brand

SPS Europe

Type

SPIN150i



Contact

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Organisation

Agrotechnology and Food Sciences

Department

Shared Research Facilities

Description

The SPIN150i is a single wafer spin coater designed for R&D and low volume production in the fields of e.g. MEMS, semiconductors, PV, and microfluidics. This equipment is located at Surfex (Plus Ultra, Bronland 12, Wageningen Campus). Are you interested in using this equipment or would you like to know more? You can contact Wout Knobens (Surfix) for information about the availability, technical details and possibilities for your specific application.

Technical Details

The spin coater is suitable for processing fragments as small as 5 mm up to 6" (round) substrates. It is programmable and can be used for spin recipes with multiple steps, including puddle spin coating (alternating clockwise and counterclockwise rotation).

Specifications:

- maximum spin speed 21,000 rpm;
- maximum acceleration 30,000 rpm/sec

Applications

Suitable for all typical spin processes:

- cleaning;
- rinse/dry;
- coating;
- developing;
- etching.